

AMENDMENTS TO THE CLAIMS:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) An exposure method in which a mask pattern is exposed onto a photosensitive substrate by an exposure body section, wherein if an error occurs in an air-conditioning system that air-conditions an interior of a chamber in which the exposure body section is housed or occurs in a temperature control system that controls a temperature of the exposure body section, a power supply of a control system that controls the exposure body section is shut down.
2. (Original) An exposure method according to claim 1, wherein the power supply is shut down after a predetermined length of time has passed since the error occurred in the air-conditioning system or the temperature control system.
3. (Original) An exposure method according to claim 2, wherein the predetermined length of time includes a length of time to allow an operation of the exposure body section to be stopped.
4. (Original) An exposure method according to claim 2, wherein, when an error has occurred in the air-conditioning system or the temperature control system, the predetermined length of time includes a waiting time in which a command regarding the error is awaited after the error has been announced.
5. (Original) An exposure method according to claim 4, wherein the power supply is forcibly shut down after the waiting time has passed.

6. (Original) An exposure method according to claim 1, wherein, before the power supply is shut down, an operating state of the exposure body section at the time the error occurred in the air-conditioning system or the temperature control system is stored.
7. (Original) An exposure method according to claim 1, wherein the power supply of the air-conditioning system or the temperature control system is shut down after the power supply of the control system has been shut down.
8. (Original) An exposure method in which a substrate is exposed using illumination light irradiated via a mask by an exposure body section of which at least a portion is housed within a chamber, wherein
a power supply of a second control system that controls operations of the exposure body section is shut down prior to a power supply of a first control system that controls an environment within the chamber being shut down.
9. (Original) An exposure apparatus comprising:
an exposure body section that exposes a mask pattern onto a photosensitive substrate;
and
a control system that controls operations of the exposure body section, wherein
there is provided at least one of an air-conditioning system that conditions air in a chamber in which the exposure body section is housed, and a temperature control system that controls a temperature of the exposure body section,

and there is provided a power supply shutdown system that shuts down a power supply of the control system when an error occurs in the air-conditioning system or temperature control system.

10. (Original) An exposure apparatus according to claim 9, wherein the power supply shutdown system shuts down a main power supply of the entire exposure apparatus.

11. (Original) An exposure apparatus according to claim 9, wherein the power supply shutdown system has a timer that allows a predetermined time to pass from when an error occurs in the air-conditioning system or temperature control system until the power supply is shut down.

12. (Original) An exposure apparatus according to claim 11, wherein the timer includes a first timer that allows a time required to stop an operation of the exposure body section to pass.

13. (Original) An exposure apparatus according to claim 11, wherein the power supply shutdown system has an announcing device that, when an error occurs in the air-conditioning system or temperature control system, announces the error, and the timer includes a second timer that allows a waiting time to pass in which, after the error has been announced, a command regarding the error is awaited.

14. (Original) An exposure apparatus according to claim 13, wherein the timer includes a third timer that forcibly shuts down the power supply after the waiting time of the second timer has passed.

15. (Original) An exposure apparatus according to claim 9, wherein there is provided a storage apparatus that stores an operating state of the exposure body section at the time the error occurred in the air-conditioning system or the temperature control system.

16. (Original) An exposure apparatus according to claim 9, wherein the power supply shutdown system shuts down the power supply of the air-conditioning system or the temperature control system after the power supply of the control system has been shut down.

17. (Original) An exposure apparatus that exposes a substrate using illumination light irradiated via a mask by an exposure body section of which at least a portion is housed within a chamber, wherein

the exposure apparatus comprises:
a first control system that controls an environment within the chamber;
a second control system that controls an operation of the exposure body section; and
a power supply shutdown system that shuts down a power supply of the second control system prior to shutting down a power supply of the first control system.

18. (Original) An exposure apparatus according to claim 17, wherein the first control system includes a gas supply system that supplies gas to at least a portion of the chamber, and a control system that controls supply conditions of the gas.

19. (Currently Amended) A device manufacturing method that includes a step in which, using the exposure apparatus according to ~~claims 9 or 17~~, claim 9, a device pattern is transferred onto a photosensitive layer formed on an object.

20. (New) An exposure method according to claim 1, wherein a power supply of the air-conditioning system or temperature control system is shut down after a predetermined time has passed since the error occurred, and a power supply of the control system is shut down at a timing that allows effects of the shutting down of the power supply of the air-conditioning system or temperature control system on the exposure body section to be kept within a permissible range.

21. (New) An exposure method according to claim 20, wherein a power supply of the control system is shut down after a deferment period has passed since the error occurred in order to allow an operation of the exposure body section to be stopped, and a power supply of the air-conditioning system or temperature control system is shut down substantially simultaneously with a shutting down of a power supply of the control system or after the power supply of the control system has been shut down.

22. (New) An exposure method according to claim 21 wherein measurement of the deferment period commences after a first waiting time has passed since the error occurred.

23. (New) An exposure method according to claims 21 wherein, when the power supply of the control system is shut down as a result of the main power supply of the exposure body section being shut down, the power supply of the air-conditioning system or temperature control system is shut down at the same time as the power supply of the control system is shut down.

24. (New) An exposure method according to claim 23, wherein if the main power supply is not shut down even when the deferment period has passed, the power supply of the control

system is shut down at the same time as the power supply of the air-conditioning system or temperature control system is shut down by shutting down the main power supply after the predetermined time has passed.

25. (New) An exposure method according to claim 24, wherein the predetermined time includes a second waiting time that is set after the error occurs.

26. (New) An exposure method according to claim 25, wherein the second waiting time is set longer than the first waiting time.

27. (New) An exposure method according to claim 8, wherein a deferment period is set in order to allow an operation of the exposure body section to be stopped before a power supply of the second control system is shut down.

28. (New) An exposure apparatus according to claim 9, wherein the power supply shutdown system shuts down a power supply of the air-conditioning system or temperature control system after a predetermined time has passed since the error occurred, and shuts down a power supply of the control system at a timing that allows effects of the shutting down of the power supply of the air-conditioning system or temperature control system on the exposure body section to be kept within a permissible range.

29. (New) An exposure apparatus according to claim 28, wherein the power supply control system shuts down a power supply of the control system after a deferment period has passed since the error occurred in order to allow an operation of the exposure body section to be stopped, and a power supply of the air-conditioning system or temperature control system

is shut down substantially simultaneously with a shutting down of a power supply of the control system or after the power supply of the control system has been shut down.

30. (New) An exposure apparatus according to claim 29 wherein the power supply shutdown system commences measurement of the deferment period after the first waiting time has passed since the error occurred.

31. (New) An exposure apparatus according to claims 29 wherein, when the power supply control system shuts down the power supply of the control system as a result of the main power supply of the exposure body section being shut down, the power supply of the air-conditioning system or temperature control system is shut down at the same time as the power supply of the control system is shut down.

32. (New) An exposure apparatus according to claim 31, wherein if the main power supply is not shut down even when the deferment period has passed, the power supply control system shuts down the power supply of the control system at the same time as the power supply of the air-conditioning system or temperature control system is shut down by shutting down the main power supply after the predetermined time has passed.

33. (New) An exposure apparatus according to claim 32, wherein the predetermined time includes a second waiting time that is set after the error occurs.

34. (New) An exposure apparatus according to claim 33, wherein the second waiting time is set longer than the first waiting time.

35. (New) An exposure apparatus according to claim 17, wherein a deferment period is set in order to allow an operation of the exposure body section to be stopped before a power supply of the second control system is shut down by the power supply shutdown system.